



In re Application of:  
Nguyen, et al.

Serial No.: 09/912,103

Confirmation No.: 4476

Filed: July 23, 2001

**For: Selective Etching of Organosilicate  
Films Over Silicon Oxide Stop Etch  
Layers**

Commissioner for Patents  
Washington, D.C. 20231

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Group Art Unit: 1746

Examiner: Khiem D. Nguyen

**CERTIFICATE OF MAILING**  
**37 CFR 1.8**

I hereby certify that this correspondence is being deposited on November 12, 2002 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.

11/12/02  
Date

Kevin 2/22

Signature

Dear Sir:

**RESPONSE TO OFFICE ACTION DATED AUGUST 12, 2002**

In response to the Office Action dated August 12, 2002, having a shortened statutory period for response set to expire on November 12, 2002, Applicant requests entry and consideration of the following amendments and remarks. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/5619/DSM/LOW K/JW, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

## IN THE DRAWINGS

Applicants propose submission of a page of formal drawings including figures 4f and 4g as shown in a separate request for correction of the drawings. The submitted page of formal drawings includes figures 4f and 4g that were inadvertently omitted from the application. The figures conform to the written description of the invention without adding new matter.